

## Solution-Processed Light Induced Multilevel Non-volatile Wearable Memory Device Based on $\text{CsPb}_2\text{Br}_5$ Perovskite

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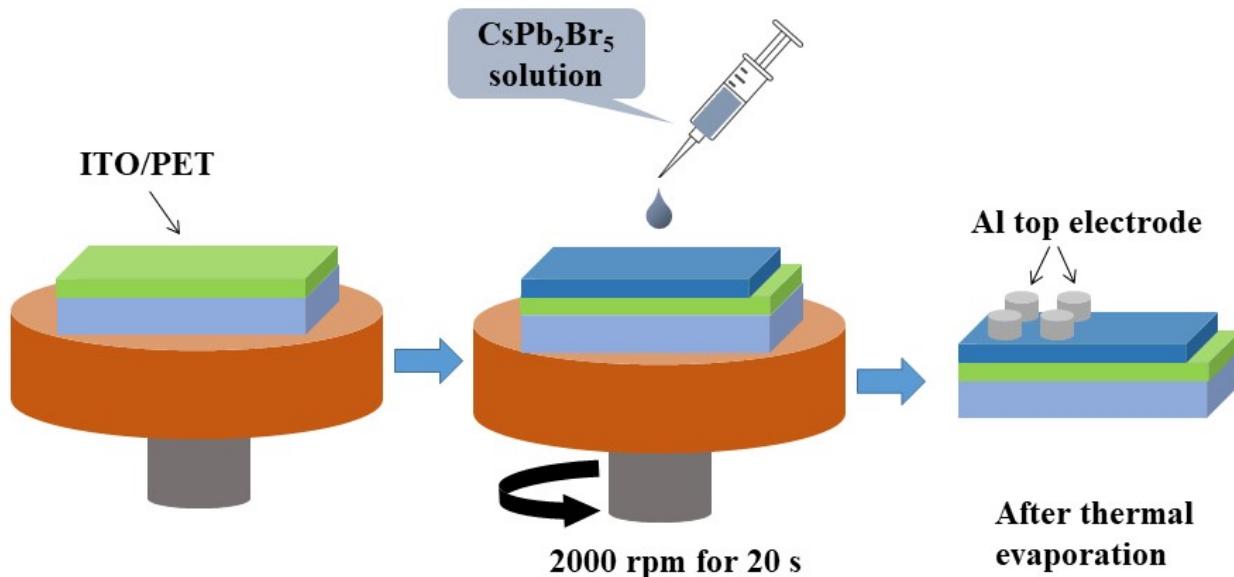
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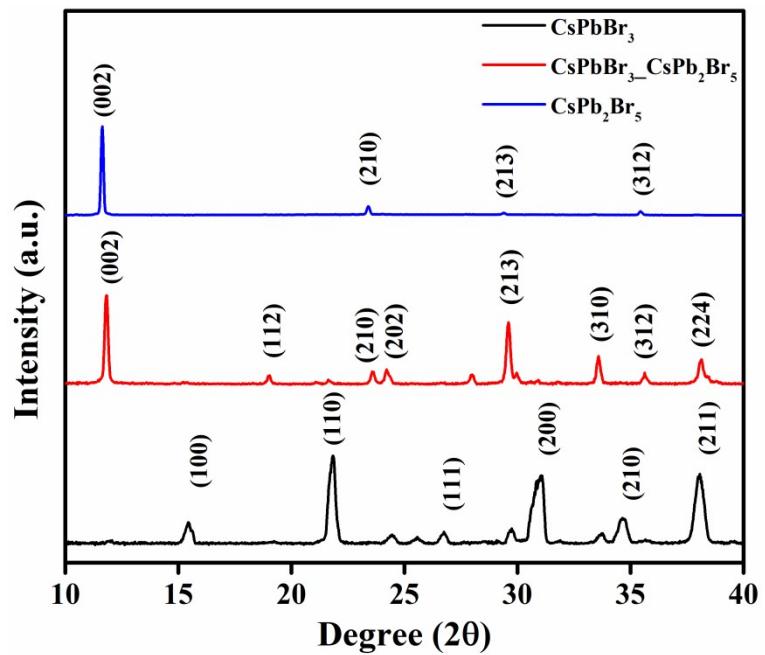
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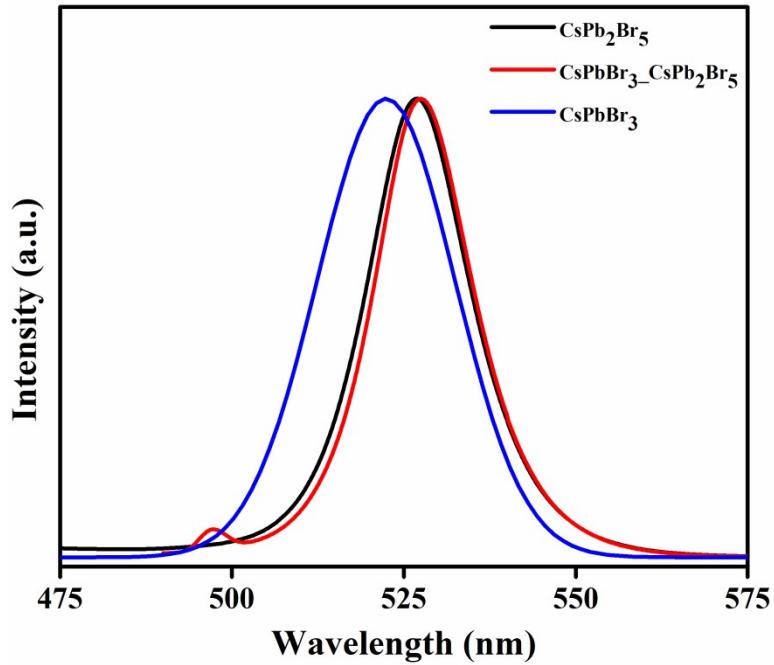
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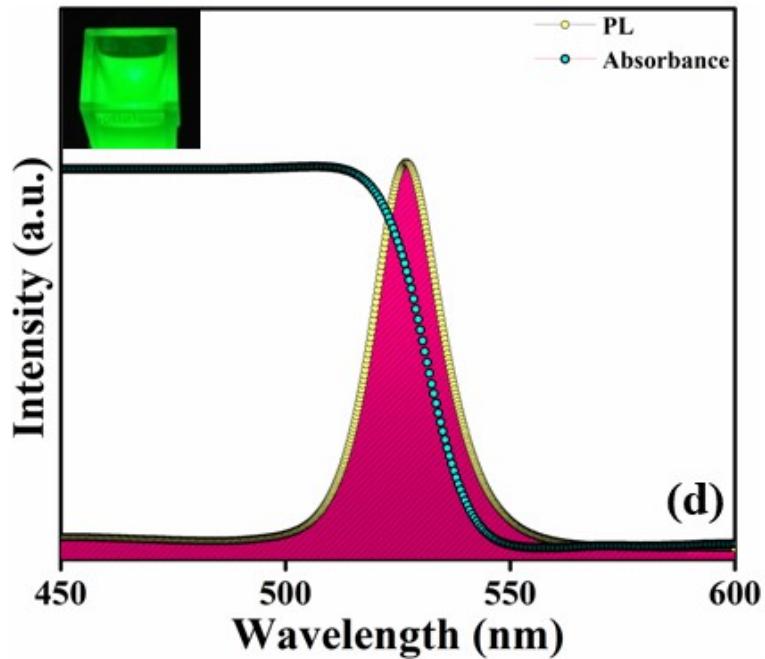
**Figure S1:** Schematic illustration of the device fabrication.



**Figure S2:** XRD profile of CsPb<sub>2</sub>Br<sub>5</sub> is compared with pure CsPbBr<sub>3</sub> and CsPb<sub>2</sub>Br<sub>5</sub>-CsPbBr<sub>3</sub>.



**Figure S3:** Photoluminescence analysis of  $\text{CsPb}_2\text{Br}_5$  is compared with pure  $\text{CsPbBr}_3$  and  $\text{CsPb}_2\text{Br}_5\text{-CsPbBr}_3$ .



**Figure S4:** UV-vis absorbance and PL spectra of the  $\text{CsPb}_2\text{Br}_5$ .

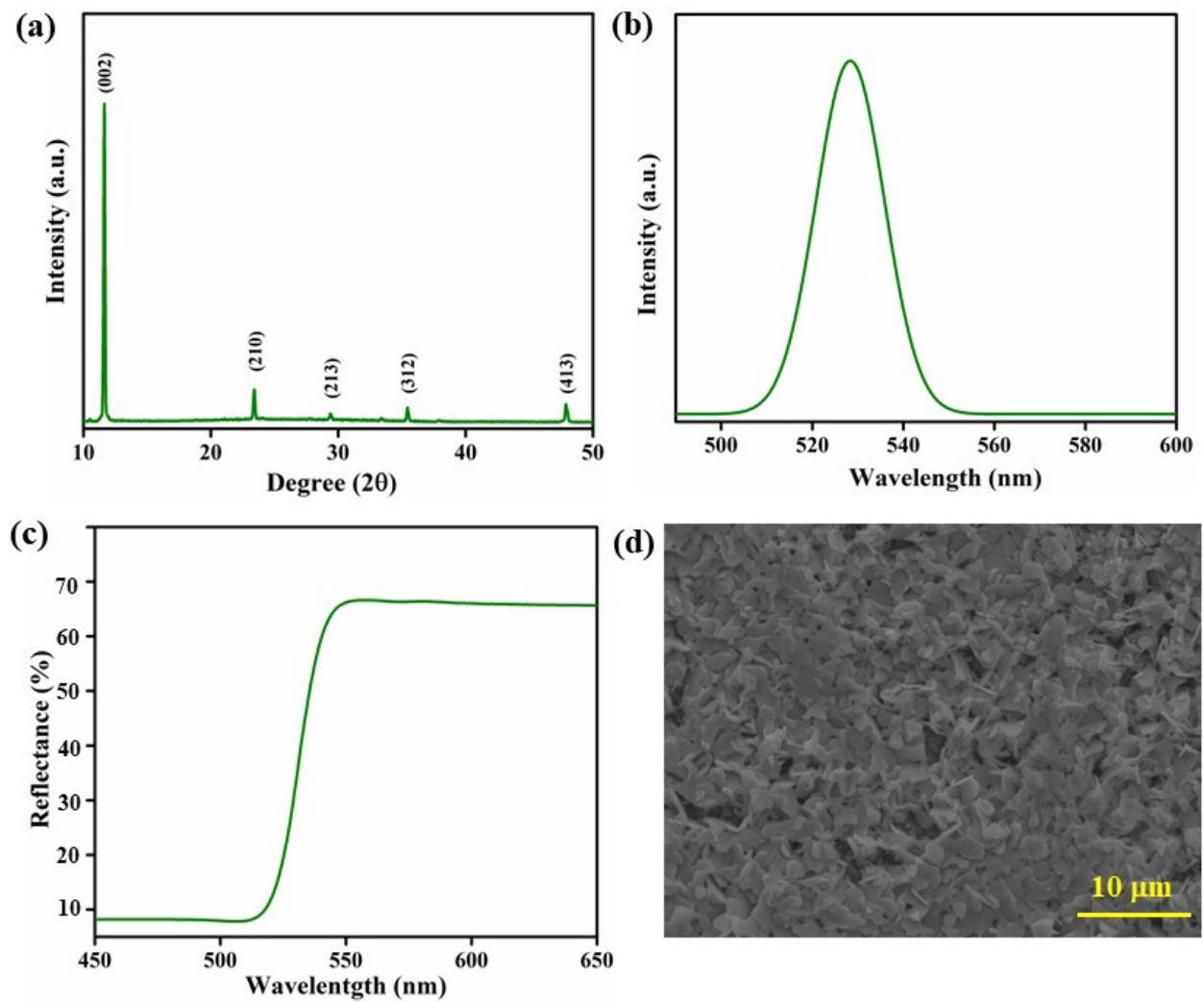
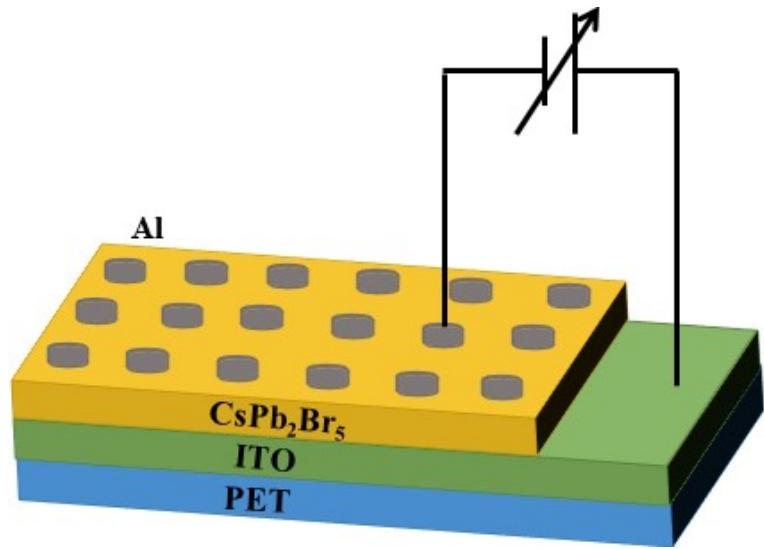
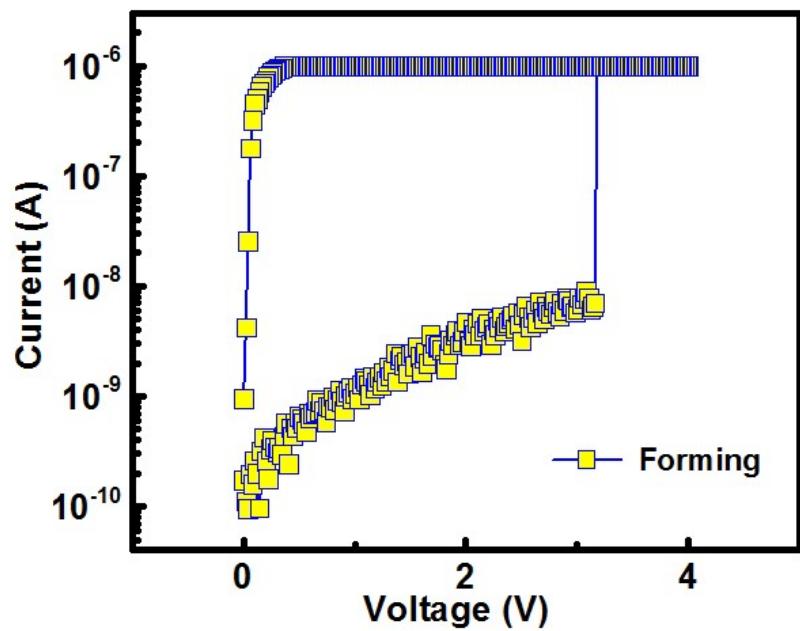


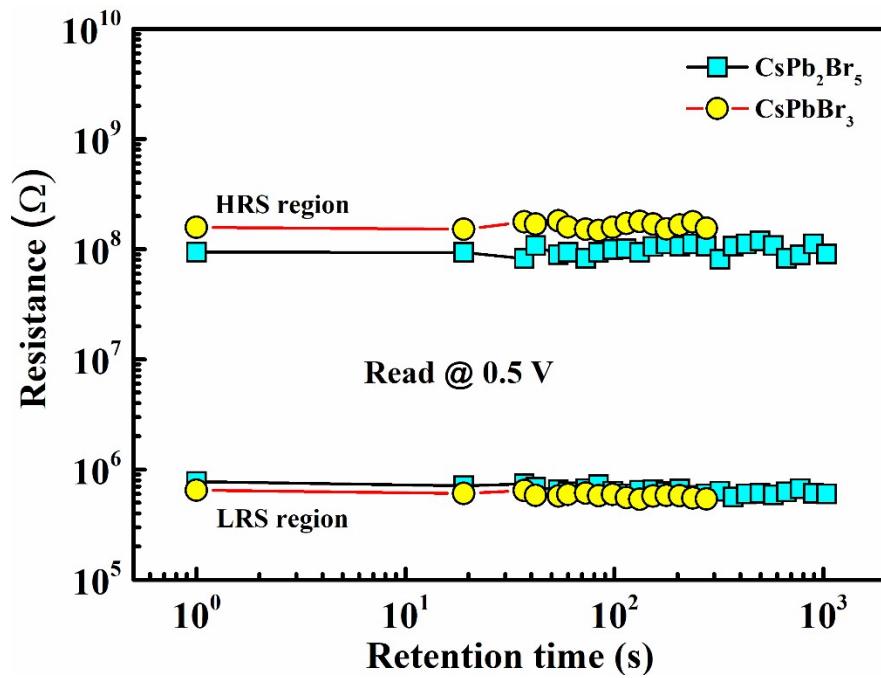
Figure S5: XRD, PL, UV-Vis and FESEM of the perovskite film.



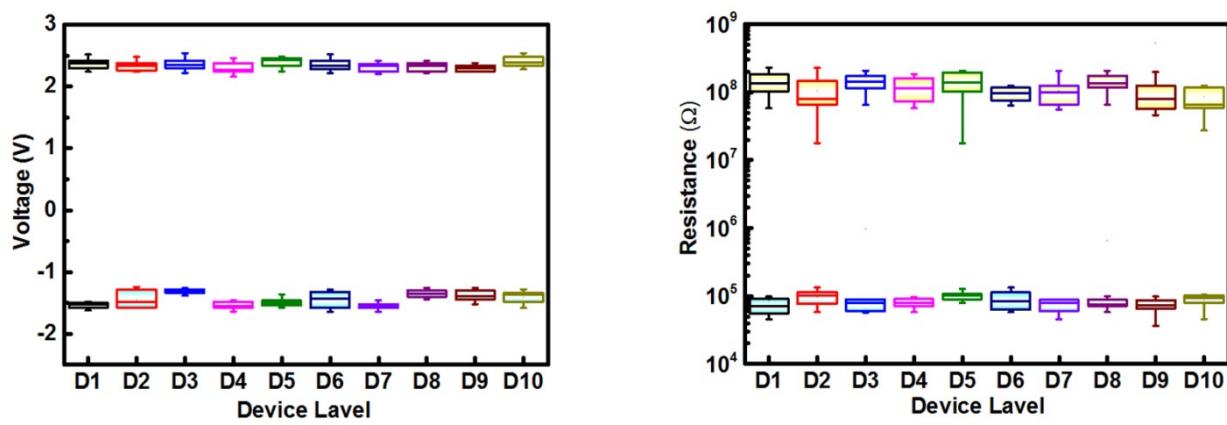
**Figure S6:** Schematic diagram of the designed memory device.



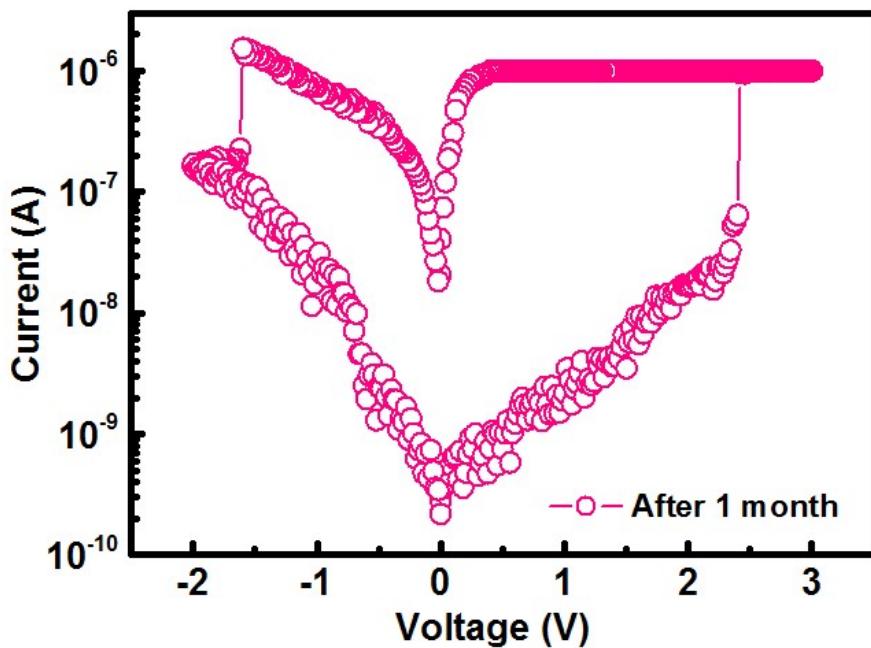
**Figure S7:** Forming process of the Al/CsPb<sub>2</sub>Br<sub>5</sub>/ITO device.



**Figure S8:** Performance comparison with  $\text{CsPbBr}_3$



**Figure S9:** Statistical distribution of (a) the switching voltage (b) LRS and HRS for various  $\text{Al}/\text{CsPb}_2\text{Br}_5/\text{ITO}$  memory cells.



**Figure S10:** I-V curve of the Al/CsPb<sub>2</sub>Br<sub>5</sub>/ITO/PET device after 1 month.

**Table S1:** Comparison of perovskite-based resistive memory devices with the proposed device

Sl. No .	Material	Device Structure	SET/RE SET Voltage	On/off ratio	Endurance (Cycle)	Bending cycle	Ref.
1	CsPbBr <sub>3</sub>	Al/CsPbBr <sub>3</sub> /PEDOT: PSS/ITO/PET	-0.6/1.7	10 <sup>2</sup>	50	100	1
2	CsBi <sub>3</sub> I <sub>10</sub>	Al/CsPbBr <sub>3</sub> / ITO substrate	-1.7/0.9	10 <sup>3</sup>	150	-	2
3	CsPb <sub>1-x</sub> Bi <sub>x</sub> I <sub>3</sub>	Ag/CsPb <sub>1-x</sub> Bi <sub>x</sub> I <sub>3</sub> /ITO	-3.6/4	10 <sup>2</sup>	500	-	3
4	MA <sub>3</sub> Bi <sub>2</sub> I <sub>9</sub>	Au/MA <sub>3</sub> Bi <sub>2</sub> I <sub>9</sub> /ITO	-0.6/1.5	10 <sup>2</sup>	300	-	4
5	MAPbI <sub>3-x</sub> Cl <sub>x</sub>	Au/MAPbI <sub>3-x</sub> Cl <sub>x</sub> /FT O	0.9/-0.65	10	100	-	5
6	MAPbI <sub>3</sub>	Au/MAPbI <sub>3</sub> /ITO/PET	0.7/-0.5	10	400	-	6
7	Cs <sub>4</sub> PbBr <sub>6</sub>	Au/Cs <sub>4</sub> PbBr <sub>6</sub> /PEDOT :PSS/ITO			100		7
8	CsPb <sub>2</sub> Br <sub>5</sub>	Al/CsPb <sub>2</sub> Br <sub>5</sub> /ITO/PE T	2.5/-2	10	100	500	This work

## References

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